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Supporting Information

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**Ink-Jet Printable, Self-Assembled, and Chemically
Crosslinked Ion-Gel as Electrolyte for Thin Film, Printable
Transistors**

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1. Experimental Section

Preparation of PVA/PEMA ion-gel ink and film: Poly(vinyl alcohol) (PVA, Mw:100,000, Sigma Aldrich) and poly(ethylene-*alt*-maleic-anhydride) (PEMA, Mw: 100,000 - 500,000, Sigma Aldrich) were separately dissolved in dimethyl sulfoxide (DMSO) and stirred at 60 °C. The weight ratio of PVA and PEMA was 70:30. After cooling down to room temperature (RT), PVA and PEMA solutions were mixed and stirred at RT for 2 h. The solution was filtered by a 13 mm syringe filter (Acrodisc, 0.45 µm Nylon membrane). After filtration, 1-ethyl-3-methylimidazolium trifluoromethanesulfonate ([EMIM][OTf], Sigma Aldrich) was added into the solution.

Characterization of PVA, PEMA, and PVA/PEMA ion-gel: The dried films of PVA/PEMA gel and ion-gel were cut in disks with 12 mm of diameters (Area: 1.13 cm²) and assembled in two stainless steel electrodes for impedance measurements. A Biologic SP 150 device with low current option was used to perform impedance spectroscopy. The sweeping frequency range was from 300 kHz to 1 Hz, and the voltage amplitude was fixed to 10 mV. Fourier-transform infrared (FTIR) spectroscopy (Perkin Elmer) was performed, scanning 12 times from 2000 cm⁻¹ to 500 cm⁻¹. For the measurement, four different films of PVA, PEMA and PVA/PEMA gel and ion-gel were prepared by drying on petri dish at 50 °C for 2 days. Scanning electron microscopy (SEM) was performed on a ZEISS Leo 1530. Images were taken at an acceleration voltage of 5 kV and a magnification of 10000. The samples were sputtered with a thin gold layer of approximate 10 nm thickness using a Cressington Sputter Coater 108 auto.

Fabrication and characterization of electrolyte-gated transistors (EGTs): In₂O₃ channels were prepared by ink-jet printing and subsequent annealing using indium oxide precursor inks consisting of 0.05 M In(NO₃)₃ dissolved in deionized water (D.I. water) and glycerol. The In₂O₃ precursor ink was filtered through a hydrophilic syringe filter (0.45 µm, polyvinylidene fluoride (PVDF)), and printed by a Dimatix 2831 ink-jet printer (Fujifilm).

Gate, source and drain electrode were patterned on indium tin oxide (ITO) substrate by e-beam lithography. Channel width and length are 600 μm and 20 μm , respectively. After printing, the printed structure was annealed at 400 $^{\circ}\text{C}$ for 2 h, afterwards, the PVA/PEMA ion-gel ink was ink-jet printed on the In_2O_3 channel. The nozzle temperature was 25 $^{\circ}\text{C}$, and the substrate temperature was set to 40 $^{\circ}\text{C}$. After drying, PEDOT:PSS as top-gate electrode was printed on the ion-gel and dried at 60 $^{\circ}\text{C}$ for 30 min. The fabricated EGTs were characterized by an Agilent 4156 C semiconductor analyzer and a Yokogawa DL6104 digital oscilloscope. The potential scan rate for measurement was set to 0.2 V s^{-1} .

2. Supplementary figure

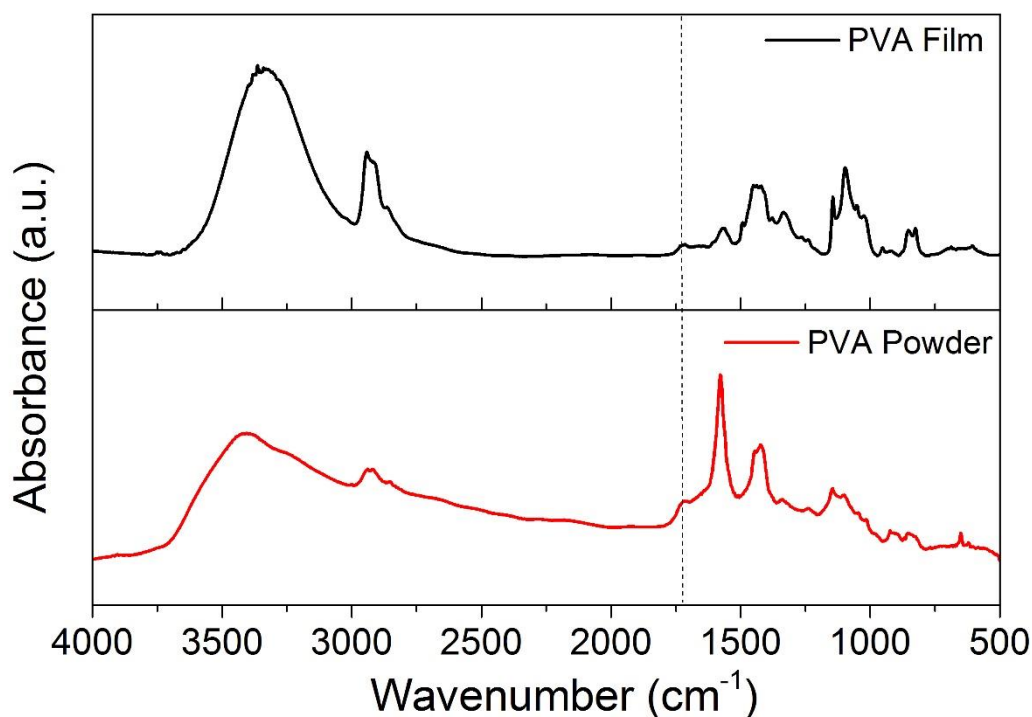


Figure S1. FT-IR absorbance spectrum of PVA film (black) and PVA pellet (red). PVA powder was pelletized with commercial PVA and KBr by hydraulic pressure.

Figure S1: FT-IR analysis was carried out to determine that C=O band of PVA film at ~ 1720 results from C=O band of poly(vinyl acetate) (PVa). To make a PVA pellet, commercial PVA powder (Sigma Aldrich) and potassium bromide (KBr, Merck) were pelletized by a hydraulic pressure. In the absorbance spectra of the PVA pellet, the C=O band is clearly observed at ~ 1720 cm⁻¹, indicating that commercial PVA powder contains a small amount of PVa, which is not hydrolyzed in PVA production, and also clarifying that C=O band at ~ 1720 cm⁻¹ in PVA film is not created during the film-making process.

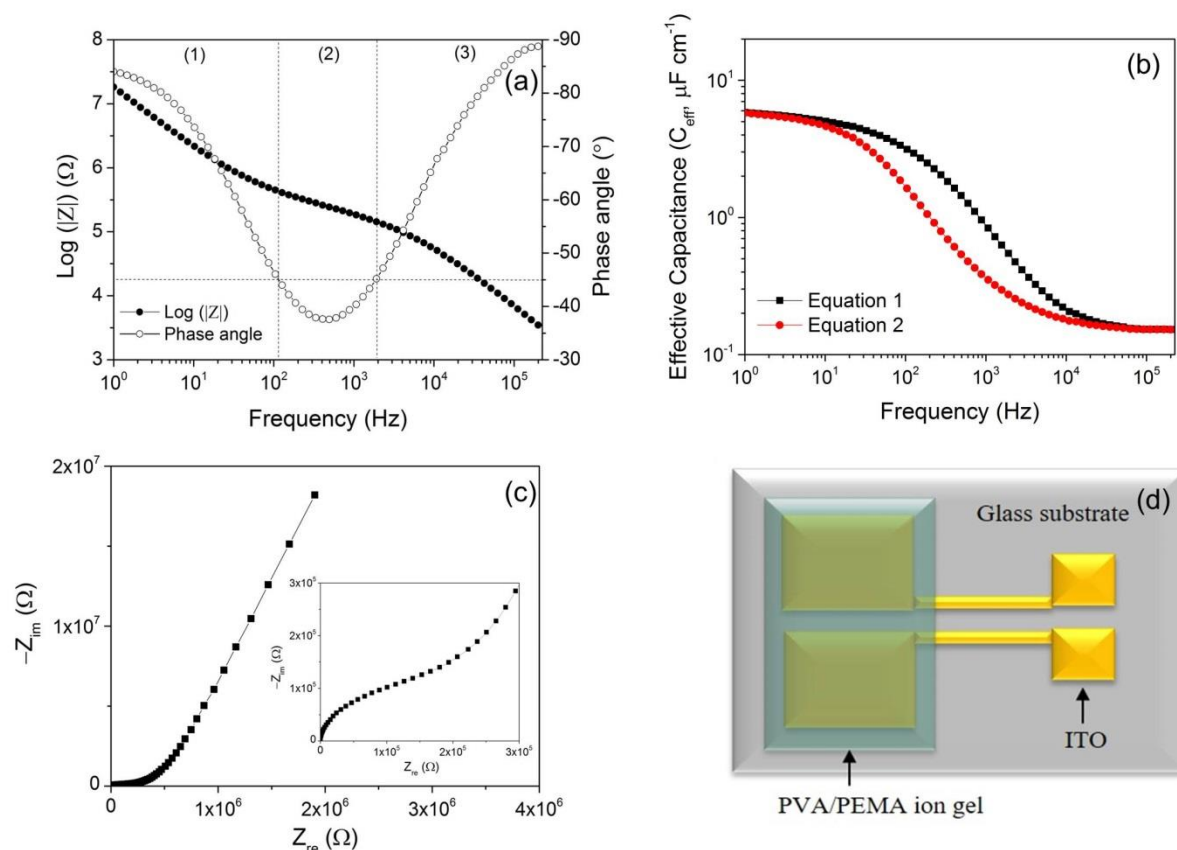


Figure S2. Impedance results of PVA/PEMA ion-gel in in-plane substrate; (a) Bode plot of $\log(|Z|)$ versus frequency, (b) C_{eff} versus frequency plot, (c) Nyquist plot, and (d) Schematic image of in-plane ITO electrodes patterned by e-beam laser. PVA/PEMA ion-gel is printed on a patterned electrode ($500 \times 300 \mu\text{m}$) by ink-jet printer.

Figure S2: In-plane ITO electrodes patterned on the glass substrate by e-beam laser were prepared to identify C_{eff} and frequency-dependent behavior of ink-jet printed ion-gel. Compared to ion-gel film, frequency-dependent plots of $\log(|Z|)$, phase angle, and C_{eff} are shifted to low-frequency range. The plots clearly show resistive and capacitive behaviors according to the applied frequency, and even dipole relaxation behavior is observed in high-frequency ranges. Considering the frequency shift, the impedance result of an ink-jet printed ion-gel is corresponding to that of ion-gel film.

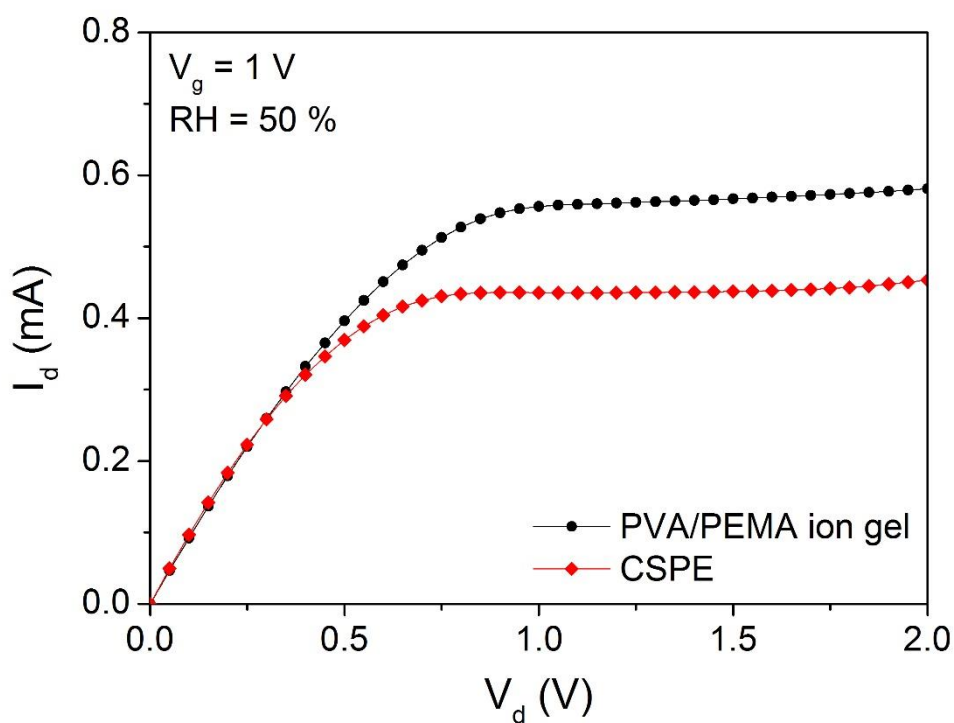


Figure S3. Drain-source voltage (V_d) versus drain-source current (I_d) plots of PVA/PEMA ion-gel and CSPE-gated transistors at 1 V_g and relative humidity (RH) of 50 %.

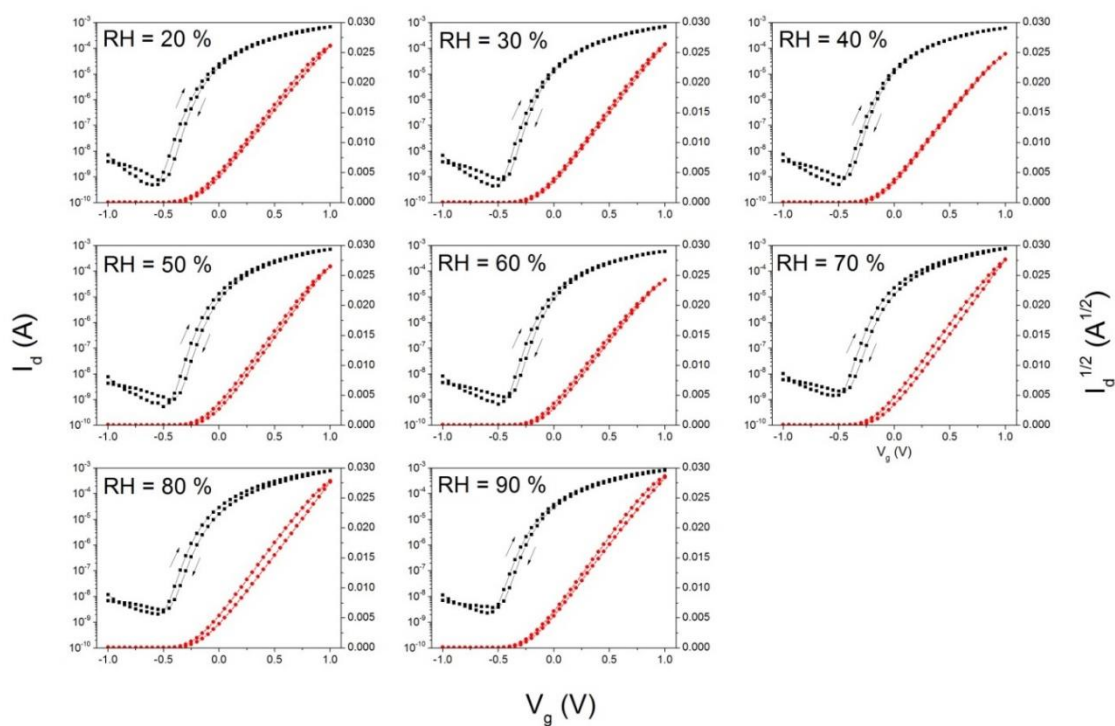


Figure S4. V_g versus I_d and $I_d^{1/2}$ plots of PVA/PEMA ion-gel-gated transistors at 1 V_d and different RH from 20 % to 90 %.

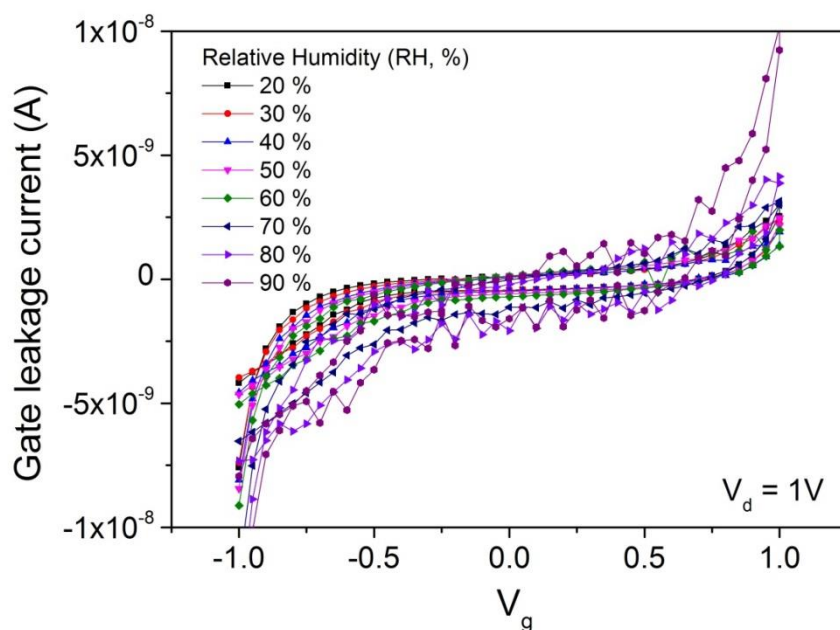


Figure S5. V_g versus gate current (I_g) plots of PVA/PEMA ion-gel-gated transistors at 1 V_d and different RH from 20 % to 90 %.

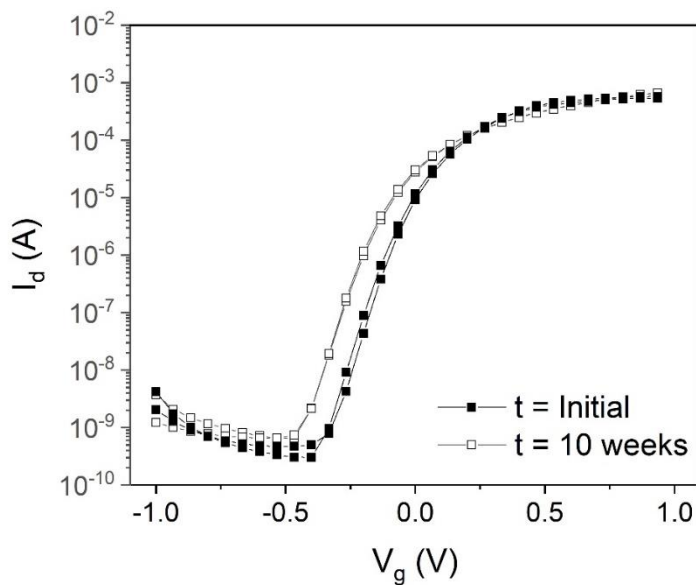


Figure S6. Gate-source voltage (V_g) versus drain-source current (I_d) plot for durability test of ion gel-gated transistors. Drain voltage (V_d) is 1 V. RH is 50 %. The sample is aged for 10 weeks in room condition.

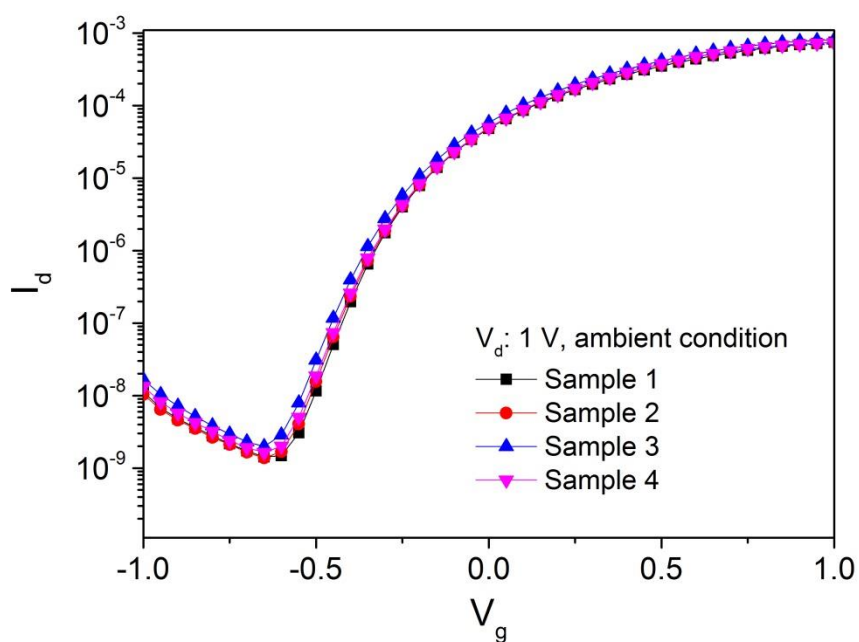


Figure S7. V_g versus I_d plot for reproduced ion gel-gated transistors (V_d is 1 V) under ambient conditions. Channel width and length are 600 μm and 20 μm , respectively. Four samples of EGTs were sequentially measured in the same condition to show experimental consistency.

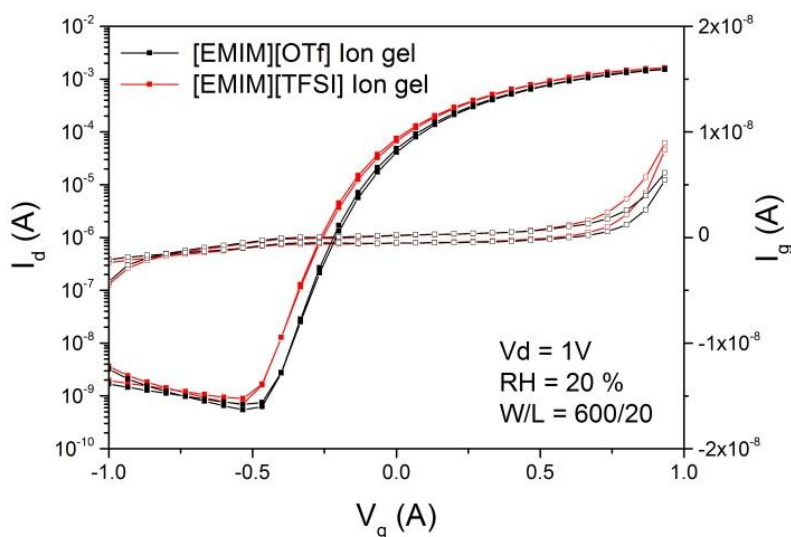


Figure S8. V_g versus I_d and I_g plot of ion gel-gated transistors. Two different ionic liquid of [EMIM][OTf] and [EMIM][TFSI] were used for ion gel. The ink ratios, fabrication, and measurement conditions of ion gels are the same. V_d is 1 V and RH is 20 %.

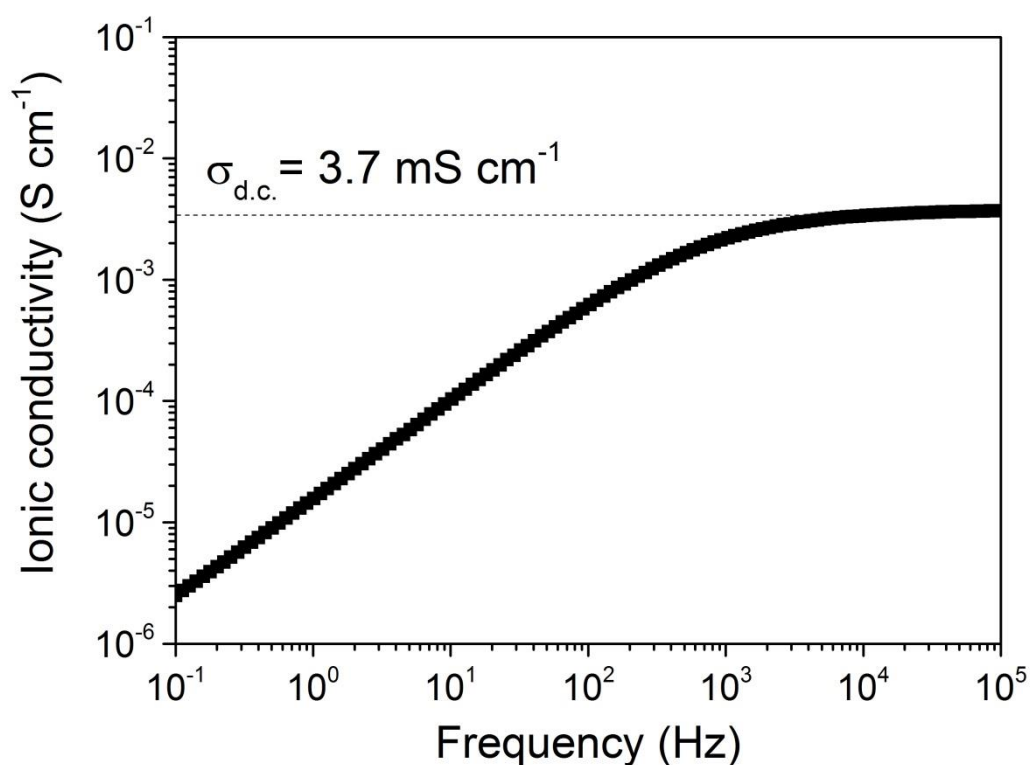


Figure S9. Ionic conductivity versus frequency plot of [EMIM][TFSI]-based ion gel. Ionic conductivity is calculated with the result of impedance spectroscopy. The thickness and diameter of ion gel film are 0.9 mm and 12 mm.

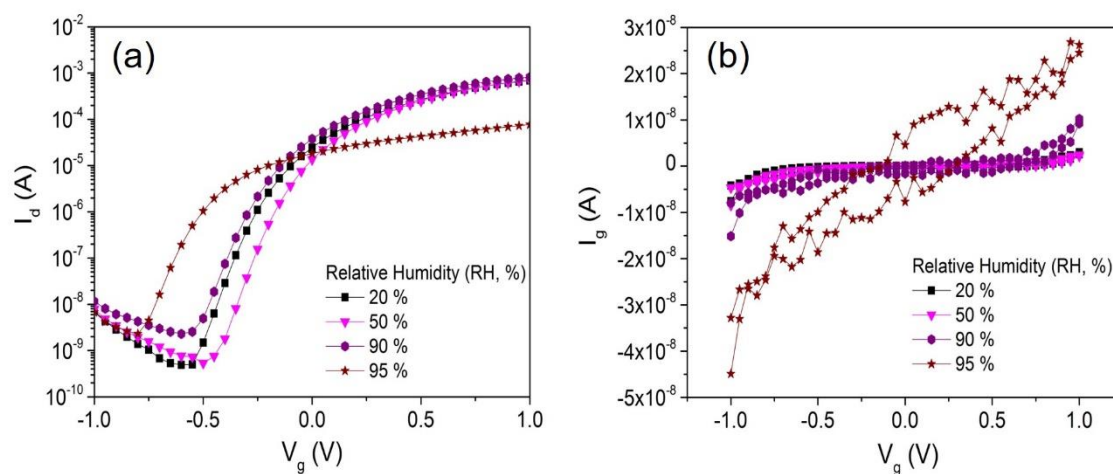


Figure S10. (a) V_g versus I_d plots and (b) V_g versus I_g plots of PVA/PEMA ion-gel-gated transistors at 1 V_d and different RH condition.